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Contents

vii Conference Committee

	X-RAY METROLOGY I
13620 02	Applications of computer-generated holograms for measuring x-ray and EUV optics (Invited Paper) [13620-1]
13620 03	Binary pseudo-random array standard for EUV lithography tool characterization [13620-2]
	X-RAY METROLOGY II
13620 04	Methodology for metrology and optimal figure tuning of bendable mirrors developed at the Advanced Light Source $[13620\text{-}5]$
	V DAY METROLOGY III
	X-RAY METROLOGY III
13620 05	Demonstration of enhanced lateral resolution in Fizeau interferometry using a tilted binary pseudo-random array test sample [13620-8]
13620 06	Development and experimental validation of an in-vacuum long trace profiler for high-precision x-ray optics metrology [13620-10]
	SOURCES AND INSTRUMENTATION
13620 07	Al-driven automatic optimization of nano-focused beams and wavefronts at the APS-U [13620-12]
13620 08	Assessing adaptive optics for fast polarization switching of synchrotron light for x-ray magnetic circular dichroism [13620-14]
13620 09	Lab-based neutron sources and instruments [13620-15]
	X-RAY MIRRORS
13620 0A	Development of ultrathin deformable mirror for a novel sub-10nm focusing optical system [13620-16]
13620 OB	X-ray mirror polishing at atomic-level accuracy using PMMA tools in water [13620-17]

13620 OC	Development of fabrication process for steeply curved x-ray mirror using electroformed substrate [13620-18]
13620 OD	Development of thin deformable x-ray mirrors for synchrotron applications [13620-21]
	FOCUSING OPTICS
13620 OE	Aberration calculation and image reconstruction in Laue lenses made of bent crystals for future gamma-ray astrophysics telescopes [13620-22]
13620 OF	Advances in 3D-printed compound refractive lenses for x-ray focusing and wavefront engineering [13620-23]
13620 OG	Compact diamond x-ray lens cubes for nanofocusing [13620-24]
13620 OH	Demonstration of a dual-beam zone plate for phase-contrast coherent soft x-ray imaging [13620-25]
	NOVEL X-RAY OPTICS AND TECHNIQUES I
13620 01	Fabrication of ultra-shallow EUV gratings in silicon via ion irradiation [13620-26]
13620 OJ	Design and performance of a double bounce multilayer monochromator for the multimodal high-energy x-ray diffraction beamline 11-ID-D [13620-27]
13620 OK	Full-size lamellar grating for the cosmic beamline at ALS-U [13620-29]
	NOVEL X-RAY OPTICS AND TECHNIQUES II
13620 OL	Diamond-based gratings for x-ray wavefront sensors [13620-30]
	POSTER SESSION
13620 0M	Metrology of thin adaptive optics for x-ray beamlines [13620-34]
13620 ON	Comparison between invasive and non-invasive photon beam monitors in the tender x-ray regime for beamline diagnostics, optimization, and feedback [13620-35]
13620 00	Fabrication of saw-tooth x-ray refractive lenses aberration-corrected by a period gradient [13620-37]
13620 OP	Surface shape fitting for x-ray mirror characterization [13620-39]

13620 0Q	A review and analysis of Fourier transform spectroscopy in the soft x-ray region: advancing historical designs with modern technology [13620-40]
13620 OR	Physical optics study of mask roughness in EUV interference lithography [13620-41]
13620 OS	FEL heat load effects on the wavefront preservation, preparing for HE at LCLS-II [13620-42]
13620 OU	Phase space analysis applied to optical design of the micron x-ray protein crystallography beamline [13620-48]
13620 OV	Preliminary experiment of sub-nanoradian angle metrology system in high energy photon source [13620-49]